

## Refine Search

### Search Results -

Terms	Documents
(438/792).ccls.	269

Database:

US Pre-Grant Publication Full-Text Database  
 US Patents Full-Text Database  
 US OCR Full-Text Database  
 EPO Abstracts Database  
 JPO Abstracts Database  
 Derwent World Patents Index  
 IBM Technical Disclosure Bulletins

Search:

L10

Refine Search

Recall Text

Clear

Interrupt

### Search History

DATE: Thursday, August 04, 2005    [Printable Copy](#)    [Create Case](#)

<u>Set</u> <u>Name</u>	<u>Query</u>	<u>Hit</u> <u>Count</u>	<u>Set</u> <u>Name</u> result set
<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
<u>L10</u>	438/792.ccls.	269	<u>L10</u>
<u>L9</u>	438/763.ccls.	2928	<u>L9</u>
<u>L8</u>	L6 and ((second near3 nitride) same (concentration or ratio))	7	<u>L8</u>
<u>L7</u>	L6 and (second near3 nitride)	63	<u>L7</u>
<u>L6</u>	L5 and (copper same silicon nitride)	179	<u>L6</u>
<u>L5</u>	L4 and plasma	481	<u>L5</u>
<u>L4</u>	L3 and ((barrier or dielectric or insulator) same silicon nitride)	481	<u>L4</u>
<u>L3</u>	L2 and plasma	754	<u>L3</u>
<u>L2</u>	L1 and (silicon nitride and (silicon or nitride) near (concentration or ratio))	955	<u>L2</u>
<u>L1</u>	copper	784360	<u>L1</u>

END OF SEARCH HISTORY